

Form 1449*	Atty. Docket No.: 303.311US2	Serial No. Unknown
INFORMATION DISCLOSURE STATEMENT BY APPLICANT (Use several sheets if necessary)	Applicant: Christophe Pierrat et al.	
	Filing Date: Herewith	Group: Unknown

U.S. PATENT DOCUMENTS

**Examiner Initial	Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate
<i>JK</i>	4,608,268	08/26/1986	Shimkunas, A.R.	427	8	07/23/85
<i>A</i>	4,653,860	03/31/1987	Hendrix, J.R.	350	336	01/07/85
	4,686,162	08/11/1987	Stangl, G., et al.	430	5	10/12/84
	5,045,419	09/03/1991	Okumura, K.	430	20	12/26/89
	5,047,117	09/10/1991	Roberts	156	643	09/26/90
	5,194,345	03/16/1993	Rolfson			05/14/91
	5,194,346	03/16/1993	Rolfson, et al.	430	5	04/15/91
	5,208,125	05/04/1993	Dowrey, et al.			07/30/91
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	5,229,872	07/20/1993	Mumola, P.B.	359	40	01/21/92
	5,240,796	08/31/1993	Lee, et al.			07/09/91
	5,254,218	10/19/1993	Roberts, et al.			04/22/92
	5,281,500	01/25/1994	Cathey, et al.	430	5	09/04/91
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	5,372,901	12/13/1994	Rolfson, et al.			06/05/92
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	5,487,963	01/30/1996	Sugawara	430	5	08/26/94
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	5,546,225	08/13/1996	Shiraishi, N.	359	559	03/31/95
	5,565,286	10/15/1996	Lin, B.J.	430	005	11/17/94
	5,567,573	10/22/1996	Morton, S.G.	430	320	04/03/95
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	5,582,939	12/10/1996	Pierrat	430	5	07/10/95
	5,667,918	09/16/1997	Brainerd, et al.			06/27/95
	5,672,450	09/30/1997	Rolfson			01/23/96
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	5,691,541	11/25/1997	Ceglio, N.M., et al.	250	492	05/14/96
	5,695,896	12/09/1997	Pierrat			12/04/95
	5,698,347	12/16/1997	Bae, S.M.	430	5	03/22/96
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Examiner <i>JK, Zm</i>	Date Considered <i>9-9-01</i>
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**Examiner Initial	Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate
262	5,827,625	10/27/1998	Lucas, K., et al.	430	5	08/18/97
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**Examiner Initial	Document Number	Date	Country	Class	Subclass	Translation Yes No
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262	Ahn, C., et al., "Study of optical proximity effects using off-axis illumination with attenuated phase shift mask", <u>Proceedings of SPIE, Vol. 2440</u> , Society of Photo-Optical Instrumentation Engineers, Bellingham, WA, 222-39, (1995)
	Barouch, E., et al., "Vector aerial image with off-axis illumination", <u>Proceedings of SPIE, Vol. 1927, Pt. 2</u> , Optical/Laser Microlithography Conference, San Jose, CA, 686-708, (1993)
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	Erdelyi, M., et al., "New interferometric phase-shifting technique for sub-half-micron laser microlithography", <u>Proceedings of SPIE, Vol. 2440</u> , Society of Photo-Optical Instrumentation Engineers, Bellingham, WA, 827-37, (1995)
262	Ham, Y., et al., "Fundamental analysis on fabrication of 256 MB DRAM using the phase shift technology", <u>Proceedings of SPIE, Vol. 2197</u> , Optical/Laser Microlithography VII Conference, San Jose, CA, 243-52, (1994)

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Date Considered 9-9-97

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**EXAMINER: Initial if citation considered; whether or not citation is in conformance with MPEP 2112. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

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9/2	Kim, K., et al., "Implementation of i-line lithography to 0.30 um design rules", <u>Proceedings of SPIE, Vol. 2440</u> , Society of Photo-Optical Instrumentation Engineers, Bellingham, WA, 76-87, (1995)
10	Levenson, M.D., "Extending optical lithography to the gigabit era", <u>Microolithography World, Vol. 3, No. 4</u> , (Autumn 1994)
	Lin, B.J., "The Attenuated Phase-Shifting Mask", <u>Solid State Technology</u> , 43-47, (January, 1992)
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26	Yan, P., et al., "Sub-micron low-k//1 imaging characteristics using a DUV printing tool and binary masks", <u>Proceedings of SPIE, Vol. 2440</u> , Society of Photo-Optical Instrumentation Engineers, Bellingham, WA, 270-77, (1995)

Examiner <u>26.022</u>	Date Considered <u>9-25-95</u>
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